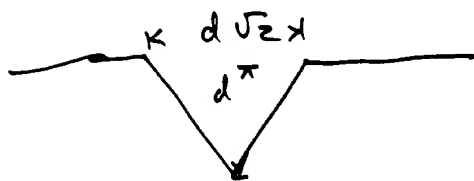
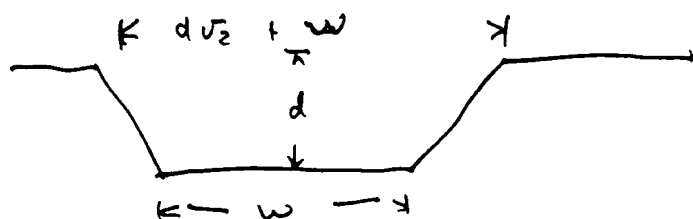


**NORTHROP EXHIBIT N**




Scribe line  $\approx 70\%$  thickness



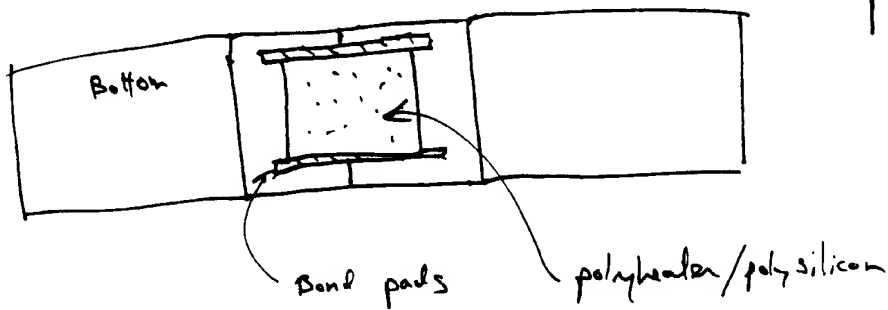
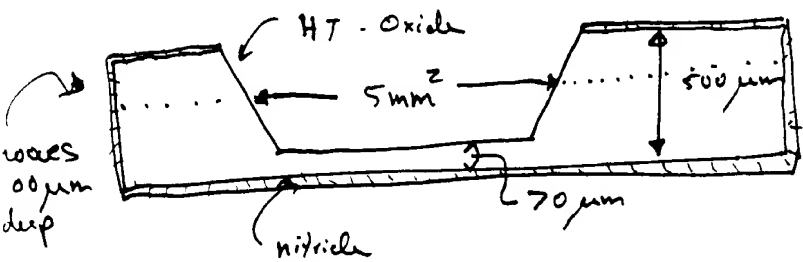
or

Syringe - U. groove



M. All 

B) Summary of rec'd design meeting with Courtney and Jim on



Processing Step 5:

- 1) RCA Clean
- 2) Thermal oxide
- 3) Polysilicon dep.
- 4) Dope poly (phos) dep. have
- 5) dep. Si<sub>3</sub>N<sub>4</sub>
- 6) Pattern well-side
  - 1) wells
  - 2) V-grooves
  - 3) Scribe lines
- 7) Plasma etch
- 8) KOH - timed etch
- 9) Strip Si<sub>3</sub>N<sub>4</sub>
- 10) Strip oxide